NOTES:

1. SUBSTRATE MATERIAL:

FUSED SILICA

2. COATING (APPLY ACROSS CLEAR APERTURE)

S1: ULTRAFAST LASER

Ravg≥99.5% REFLECTIVITY AT 780 - 820nm AT 0° AOI

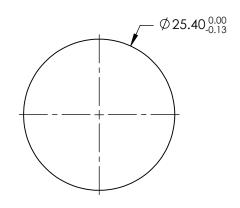
DAMAGE THRESHOLD, PULSED:

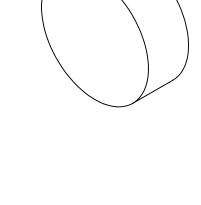
0.79 J/cm² @ 800nm, 200fs FWHM, LINEAR POLARIZATION, 1 PULSE (TYPICAL) 0.7 J/cm² @ 800nm, 200fs FWHM, 100Hz, LINEAR POLARIZATION, 1000 PULSES (TYPICAL)

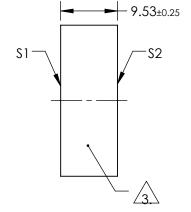
S2: NONE



4. RoHS: COMPLIANT







FOR INFORMATION ONLY:
DO NOT MANUFACTURE
PARTS TO THIS DRAWING

SPECIFICATIONS SUBJECT TO CHANGE WITHOUT NOTICE DIMENSIONS ARE FOR REFERENCE ONLY

SHAPE	S1	S2		R	Edmund Optics	®
	PLANO	PLANO	_			
SURFACE ACCURACY AT 632.8nm (P-V)	λ/6	N/A	1		800nm DWL 25.4mm DIA, ULTRAFAST HIGH	н
SURFACE QUALITY	10 - 5	COMMERCIAL POLISH	THIRD ANGLE PROJECTION	TITLE	ENERGY MIRROR 0°	•
CLEAR APERTURE	Ø21.59	N/A				ICCT
BEVEL	PROTECTIVE AS NEEDED	PROTECTIVE AS NEEDED	ALL DIMS IN mm	DWG NO		HEET OF 1